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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/768,998	01/30/2004	Hideaki Takizawa	1324.69359	4521

7590 01/24/2007  
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EXAMINER
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MCPHERSON, JOHN A

ART UNIT	PAPER NUMBER
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1756

SHORTENED STATUTORY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE
3 MONTHS	01/24/2007	PAPER

**Please find below and/or attached an Office communication concerning this application or proceeding.**

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

## Office Action Summary

Application No.

10/768,998

Applicant(s)

TAKIZAWA, HIDEAKI

Examiner

John A. McPherson

Art Unit

1756

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

### Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

### Status

- 1) ☒ Responsive to communication(s) filed on 26 October 2006.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

### Disposition of Claims

- 4) ☒ Claim(s) 1-17 is/are pending in the application.
- 4a) Of the above claim(s) 16 and 17 is/are withdrawn from consideration.
- 5) ☒ Claim(s) 2,3,5,6,8,9,11,12,14 and 15 is/are allowed.
- 6) ☒ Claim(s) 1,4,7,10 and 13 is/are rejected.
- 7) ☐ Claim(s) \_\_\_\_\_ is/are objected to.
- 8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

### Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 30 January 2004 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
- Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
- Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

### Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some \* c) ☐ None of:
- ☐ Certified copies of the priority documents have been received.
  - ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
  - ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

\* See the attached detailed Office action for a list of the certified copies not received.

### Attachment(s)

- ☒ Notice of References Cited (PTO-892)
- ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- ☒ Information Disclosure Statement(s) (PTO/SB/08)  
Paper No(s)/Mail Date 1/30/04
- ☐ Interview Summary (PTO-413)  
Paper No(s)/Mail Date. \_\_\_\_\_
- ☐ Notice of Informal Patent Application
- ☐ Other: \_\_\_\_\_

**DETAILED ACTION**

***Election/Restrictions***

1. Applicant's election without traverse of Group I, claims 1-15 in the reply filed on 10/26/06 is acknowledged.

Claims 16 and 17 withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim.

***Claim Rejections - 35 USC § 102***

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 4, 7, 10 and 13 are rejected under 35 U.S.C. 102(b) as being anticipated by US 5,026,143 to Tanaka et al. (Tanaka). Tanaka discloses a method of making an active liquid crystal matrix display panel by group exposure, wherein the TFT's in the display region are divided into a plurality of groups and patterns are formed sequentially by group. Each bus bar has a small expanded portion at positions corresponding to the group boundaries of the TFT pattern divided in group exposure (corresponding to edges of the resist pattern in the present invention). See the abstract, column 1, lines 61-66; column 3, lines 13-58; and Figure 5.

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3. Claims 1, 4, 7, 10 and 13 are rejected under 35 U.S.C. 102(b) as being anticipated by US 2002/0039841 to Takizawa (Takizawa). Takizawa discloses a method of manufacturing a thin film transistor matrix substrate in which first patterns serving as basic units are repetitively arranged using a plurality of exposure masks, in which a third region sandwiched between a first region exposed with a first mask and a second region exposed with a second mask is exposed in a complementary manner with the first and second exposure masks, repetitive unit patterns for exposing the third region being different from the first patterns. The masks are used for patterning drain bus lines and storage capacitor electrodes, whereby the bus lines or the like are provided at an edge of a basic pixel unit within the region of the same. See the abstract; paragraphs [0024], [0027], [0028] and [0048]; and Figure 1.

4. Claims 1, 4, 7, 10 and 13 are rejected under 35 U.S.C. 102(b) as being anticipated by US 6,356,320 to Chung et al. (Chung). Chung discloses a method of forming liquid crystal display comprising the steps of defining a stitching defect correcting element at an end of a gate bus line or a data bus line using a divided exposure method, wherein the width of the bus line at a border part of the divided exposure (i.e. at the edge of the resist pattern) is different from the widths of the adjacent bus lines, and eliminating the stitching defects by forming a wave shaped resistance pattern using a laser to shape or cut the stitching defect correcting element. See the abstract; column 4, lines 12-22; column 5, lines 37-53; and Figures 7 and 8.

***Allowable Subject Matter***

5. Claims 2, 3, 5, 6, 8, 9, 11, 12, 14 and 15 are allowed because in a pattern forming method for forming a wiring pattern on a substrate having a plurality of divided exposure regions as set forth in claim 2 of the present invention, the prior art does not teach or suggest the step of correcting a relative misalignment of the first and second exposure masks relative to the substrate based on a pattern width of the wiring pattern formed in the vicinity of the boundary.

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to John A. McPherson whose telephone number is (571) 272-1386. The examiner can normally be reached on Monday through Friday, 8:00 AM to 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

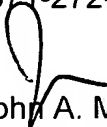
Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a

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USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.



John A. McPherson  
Primary Examiner  
Art Unit 1756

JAM  
1/17/07